Interfacial engineering eliminates energy loss at perovskite/HTL junction

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EXPERIMENTAL SECTION

Film Fabrication (TiO₂)

Fluorine-doped tin oxide (FTO, Pilkington, TEC15) glass was etched with HCl aqueous and Zn powder. The obtained glass was then cleaned with detergent, distilled water and ethanol, respectively. The blocking TiO₂ layers (bl-TiO₂) were deposited on the as-prepared FTO though spray pyrolysis method followed by calcining at 510 °C for 30 min. The mesoporous TiO₂ (mp-TiO₂) films were deposited on the above bl-TiO₂ layer by means of spin-coating the TiO₂ paste (Dyesol 30NR-T). The obtained

layers were following by heating at 510 °C for 20 min.

Solar Cell Fabrications (FAPbI₃)

The PbI₂ solution (600 mg of PbI₂ and 93 μ L of DMSO in 1 mL of DMF) was spincoated on the TiO₂/ITO substrate. The obtained films were annealed at 70 °C for 10 min. Then 100 uL of the FAI solutions (80 mg of FAI and 10 mg of MACl in 1 mL of isopropanol) were immediately spin-coated on the PbI₂ films at 5000 rpm for 20s. The intermediate films were immediately annealed at 150 °C for 20 minutes to form various perovskite films. The spiro-OMeTAD solution (25 μ L), which consists 73 mg of spiro-OMeTAD, 28 μ L of 4-tert-butyl pyridine and 17.5 μ L of lithium bis (trifl uoromethanesulfonyl) imide (Li-TFSI) solution (520 mg of Li-TSFI in 1 mL of acetonitrile) in 1 mL of CBZ, was spin-coated on the perovskite film at 3000 rpm for 20 s. Finally, Au electrode with a thickness of 60 nm was deposited by using thermal evaporation under vacuum at a constant evaporation rate of 0.6 nm s⁻¹.

Passivation Layer (BAI)

To introduce a passivation layer, 40 μ L solution of BAI (4mg) dissolved in the IPA (1 mL) was dropped on the as prepared film. Subsequently, the as-prepared films were heated at 100 °C for 15 min.

Characterization

Field emission scanning electron microscope (SEM) was used to study the topmorphology of the prepared film (FEI Sirion 200, Netherland). The crystal phase was obtained with X-ray diffraction (XRD) using Cu K α beam (X'Pert Pro, Netherland). The current-voltage curve was measured under one sun illumination (AM 1.5G) with a solar simulator (94043A, USA) equipped with Keithley 2400 source meter. XPS spectra were collected using a Thermo-Scientific Ka X-ray Photoemission Spectrometer operating at a base pressure of 5×10^{-8} mbar and using an Al anode at a power of 72 W, a hemispherical analyzer, and pass energy of 20 eV. No flood gun was used as all samples are fabricated on the FTO substrate with decent electrical conductance. Ultraviolet-visible (UV–vis) absorption spectroscopy was measured using the spectrophotometer (SOLID3700, Shimadzu Co. Ltd, Japan). Incident photon-to-electron conversion efficiency (IPCE) spectra were measured using a 300 W xenon lamp with a spectral resolution of 5 nm equipped with order sorting filters (Newport/Oriel). Steady PL, TRPL and confocal PL mapping were recorded with a laser confocal Raman spectrometer (Princeton Instruments, Acton Standard Series SP-2558) and a 405 nm laser (OBIS LX-405) using a home-built confocal microscope on a 10×10 μ m² sample area.



Figure S1 (a) Schematic illustration of the spin-coating with BAI passivation layer for fabricating perovskite layers. (b-d) XRD patterns of annealed formamidiniumbased perovskites films fabricated based on different concentrations of BAI precursor

solution.

	τ_1 (ns)	$\tau_2 (ns)$	Average τ(ns)
n-FAPbI ₃	8.01	25.83	16.87
Rel. (%)	50.3	49.7	

Table S1 The detailed τ_1 and τ_2 fitting from TRPL of n-type FAPbI₃.